

CHEMICALLY AMPLIFIED RESIST MATERIAL AND PATTERNING
METHOD USING SAME

5

ABSTRACT OF THE DISCLOSURE

A chemically amplified resist material comprising a
10 base resin and a photo acid generator having sensitivity
at the wavelength of patterning exposure; wherein, the
chemically amplified resist material further comprising
an activator that generates an acid or a radical by a
treatment other than the patterning exposure. A
15 patterning method using the same is also disclosed.